

S&A FY03 ANNUAL REVIEW MEETING

Solid State Sensors for Monitoring Hydrogen in IOF Process Streams



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Project Overview

- **Project description**

- Fabricate various Pd alloy (Au, Ni) sensor structures
- Functionalize with inorganic coatings (SiO₂, SiC, SiCN)
- Laboratory test under mixed-gas, process-like conditions
- Field test sensors to demonstrate value added

- **Objectives**

- Overcome limitations to existing technology
 - hydride phase transitions, aggressive chemical environments
- Optimize alloy composition, film morphology, coating structure

- **Overall goal**

- Develop inexpensive thin film chemical resistor technology for distributed monitoring of hydrogen in industrial process streams

Technical Merit

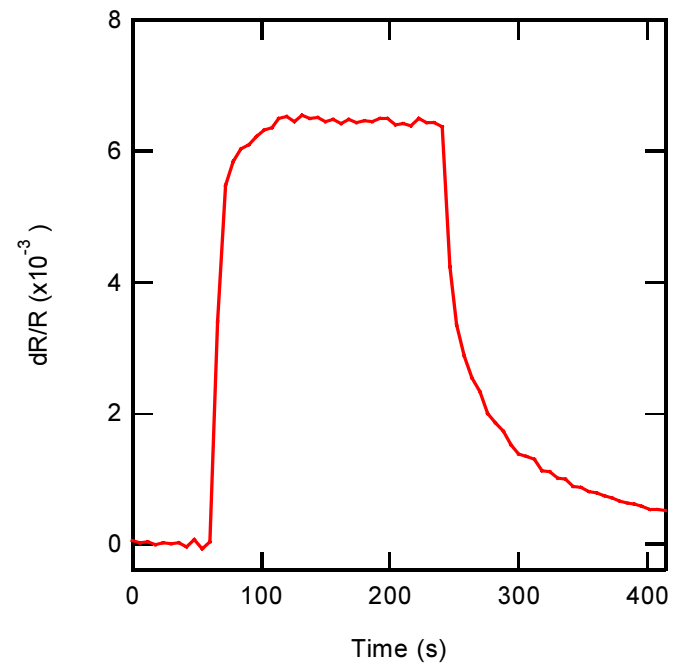
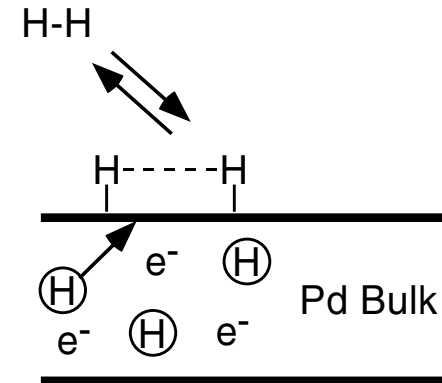
- **Measuring H₂ content of process streams critical to S&A community (Industries of the Future)**
 - Glass
 - surface defects in tin float baths
 - Chemicals
 - ammonia and polyolefin manufacture, batch hydrogenation
 - Petroleum
 - hydrogen recovery / cogeneration for oil refining
- **Application outside Industries of the Future**
 - Advancing the H₂ economy
 - generation, storage, utilization

Technical Merit

- **H₂ microsensor new technology to S&A community**
 - Current method
 - MS and GC/MS, complex instrument (\$300K per unit)
- **Extend applicability of chemical resistor**
 - Aggressive environment
 - Mixed-gas process streams
 - H₂, CH₄, C₂-C₄ species, H₂O, CO, sulfur species
 - High pressure / high temperature
- **Performance metric**
 - Simple, inexpensive, robust microsensor
 - On-line hydrogen analysis time < 5 s per data point
 - Compositional analysis accuracy < 0.1% for H₂

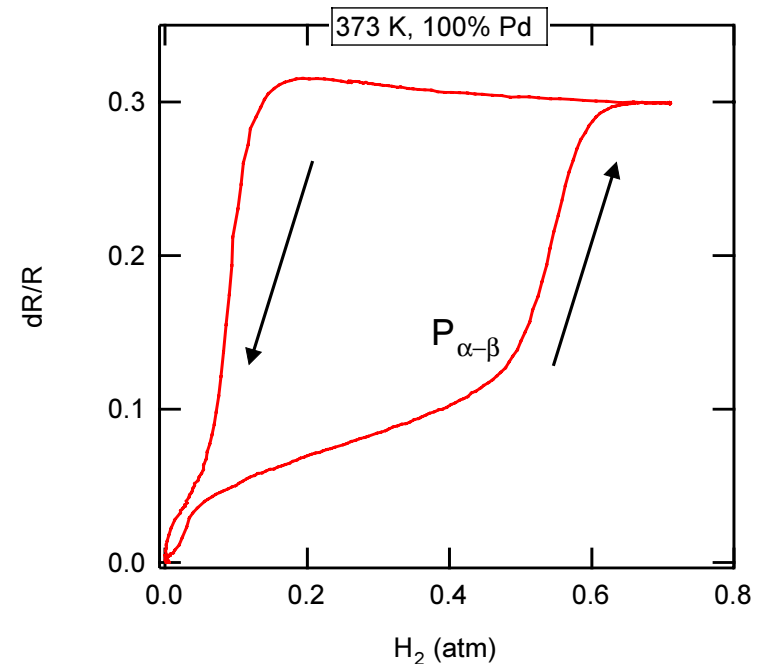
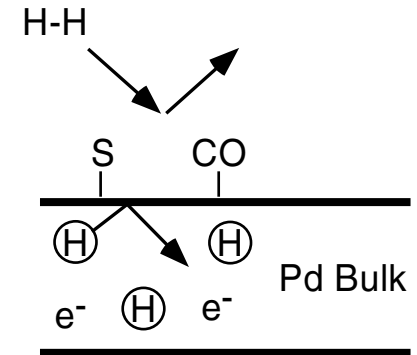
Overview of Technology

- **Thin ohmic film of transition metal alloy (Pd, Ni, Au)**
- **Principle of operation**
 - Surface chemistry moderates response
 - dissociative adsorption of H_2
 - Protons diffuse into bulk altering I-V characteristics
 - increase electrical resistance
 - measure change relative to nominal resistivity (dR/R)
- **Unique selectivity to H_2**

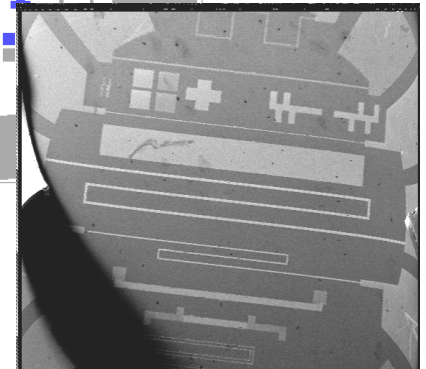
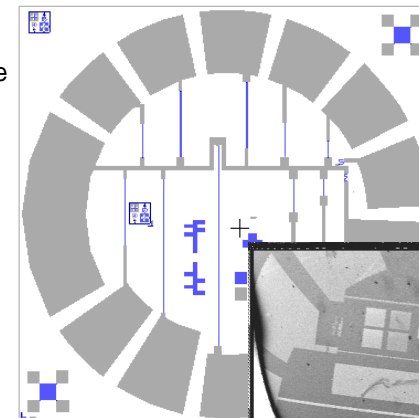
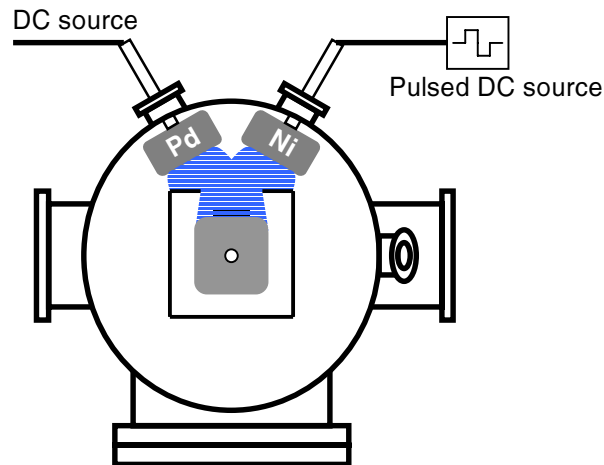
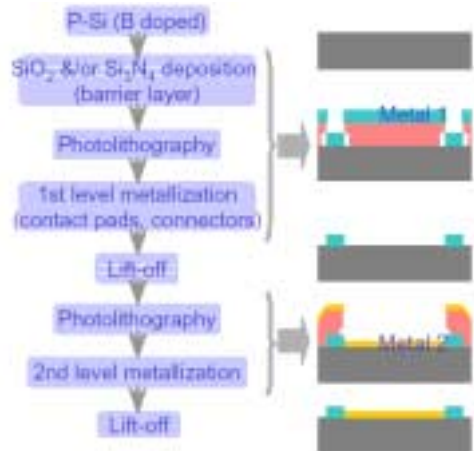


Barriers to Industrial Applications

- **Hydride phase transitions at moderate H_2 pressures**
 - $P_{\alpha-\beta} < 0.6$ atm H_2 for pure Pd
 - Increase strain in thin film
 - delaminate and destroy sensor
 - Large hysteretic effect
- **Poisoning of catalytic surface by CO and sulfur compounds (H_2S , $RR'S$, RHS)**



Design, Fabricate, and Test Sensors



■ Microfabrication (PSU)

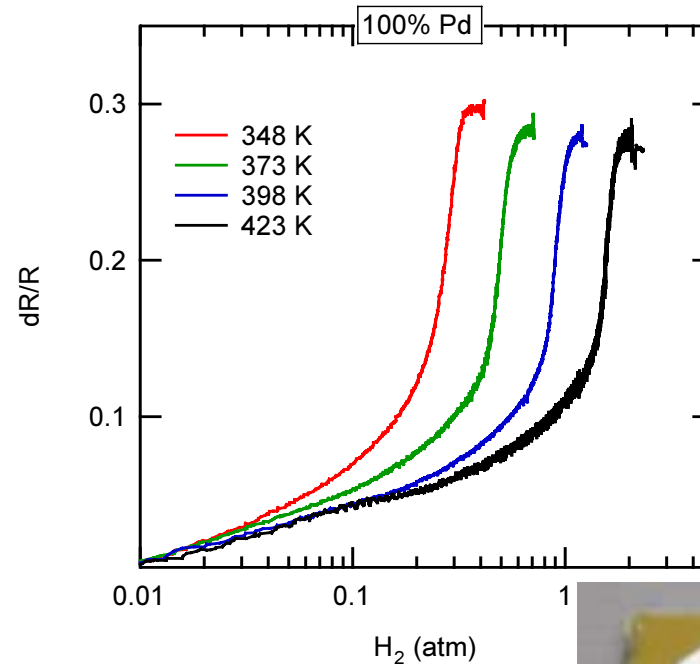
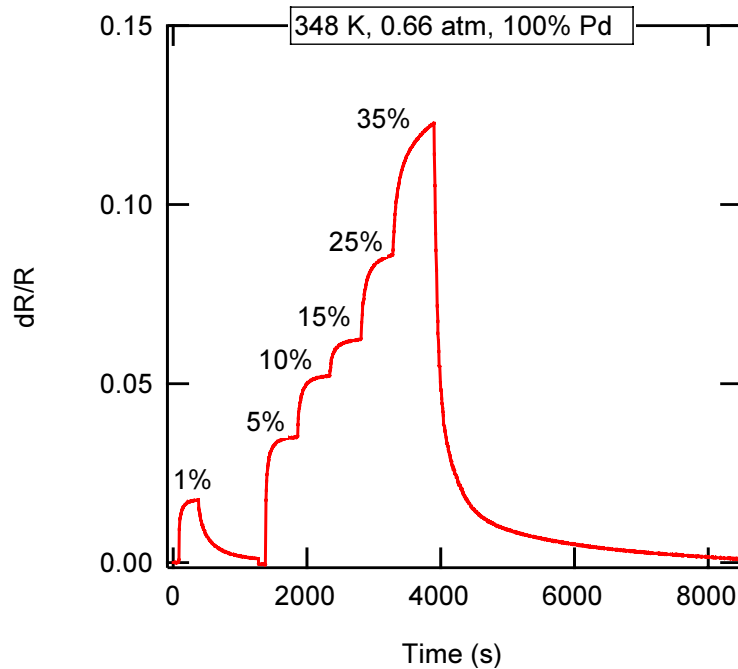
- Contact lithography, magnetron sputtering
 - precise control of film properties

■ Laboratory tests (SNL)

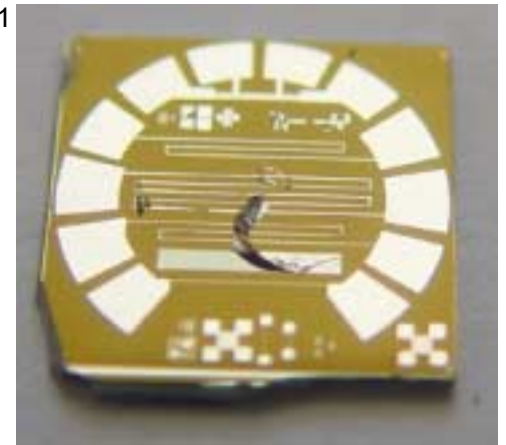
- Extensive materials evaluation capabilities
- Flow cells with integrated diagnostics
- Vacuum to 2000 psia



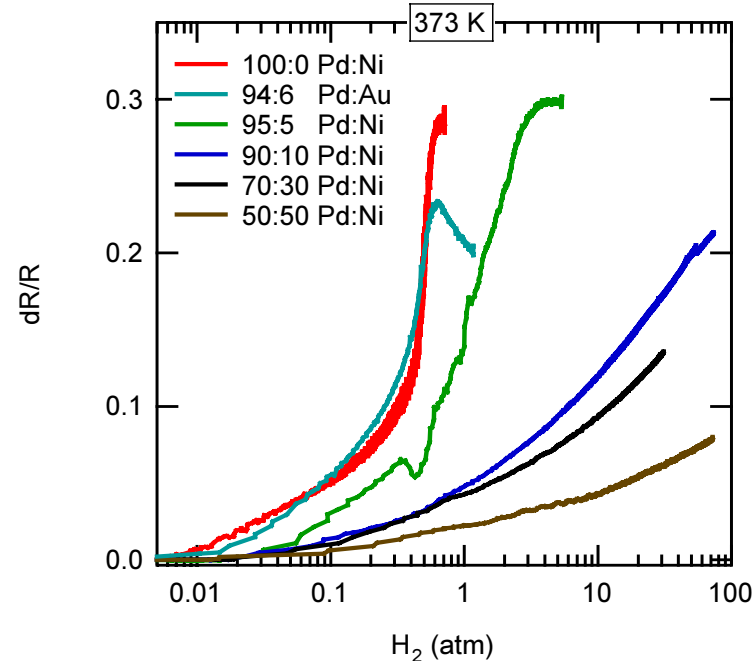
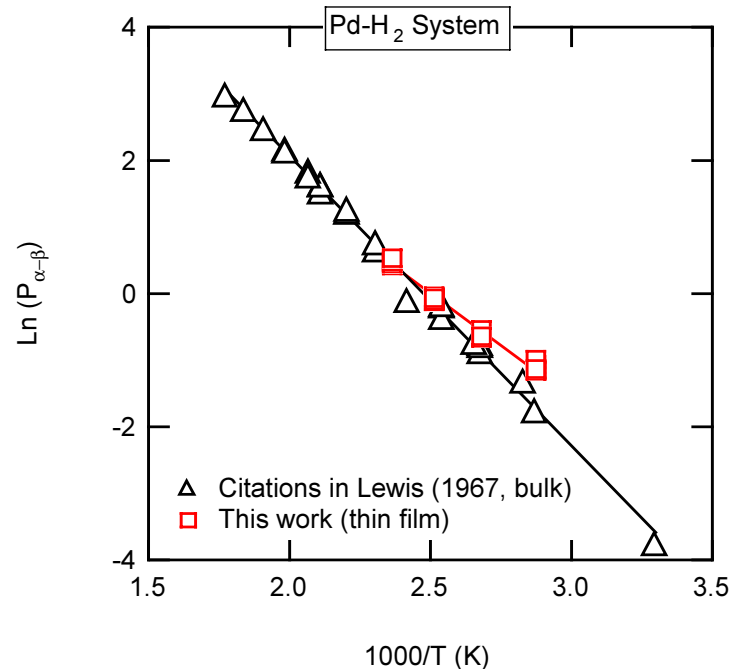
Pure Pd Chemical Resistors



- **H_2 produces a change in resistance**
 - Relatively rapid response, reversible
 - Temperature dependent uptake (Sievert's Law)
- **Phase transition results in device failure**

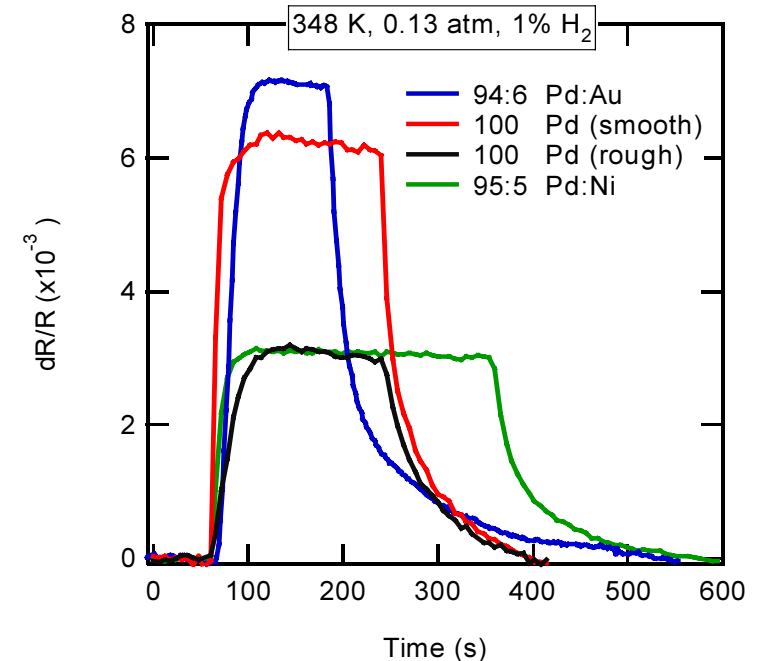
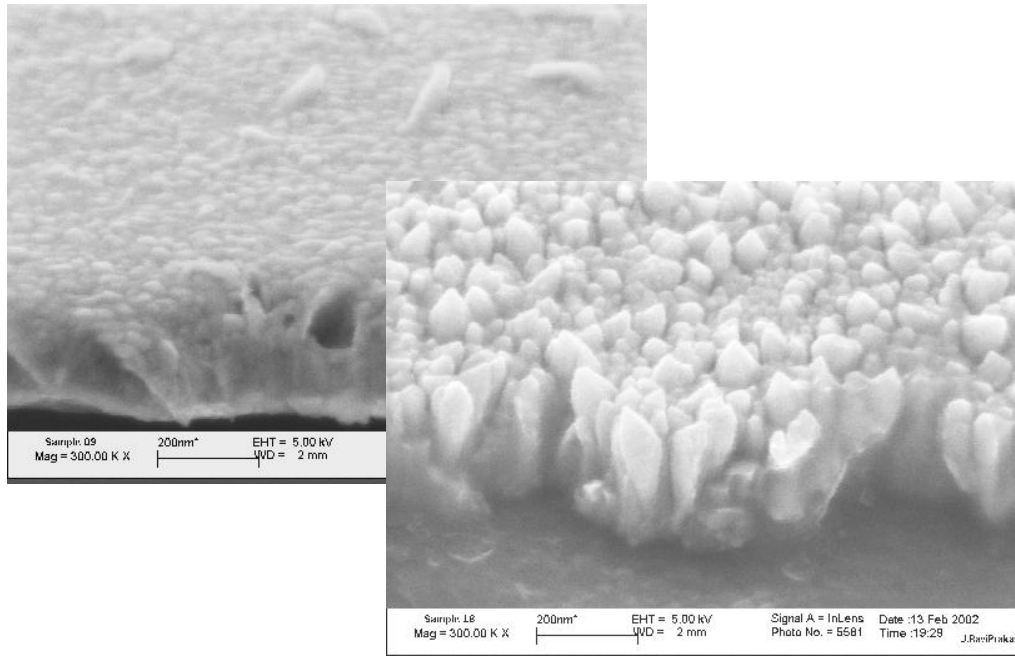


Effects of Alloy Metal and Composition



- **Thin film Pd-H₂ system like bulk material**
 - $1/T$ behavior of $P_{\alpha-\beta}$ in agreement with bulk and sintered samples
- **Alloying influences $P_{\alpha-\beta}$ hydride transition point**
 - Ni stabilizes film at the expense of sensitivity
 - Au expected to destabilize film at higher concentrations

Effects of Film Morphology



- **Alloy composition influences sensitivity**
- **Surface microstructure plays an unknown role**
 - Rough films have slower response time and lower sensitivity

Chemical Poisoning by CO

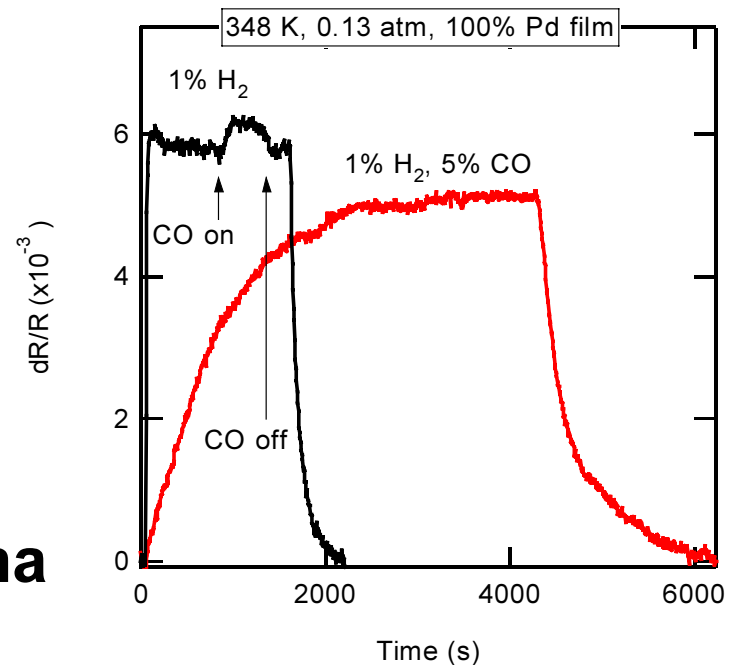
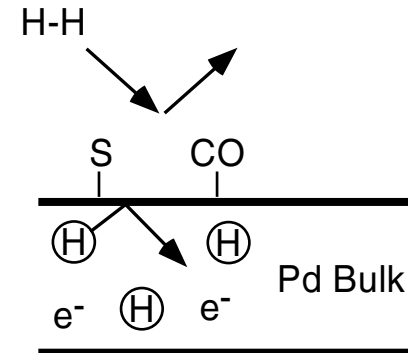
- **Surface chemistry controls response**

- Site blocking mode
 - long response times
- Trapping mode
 - attenuate H_2 sensitivity

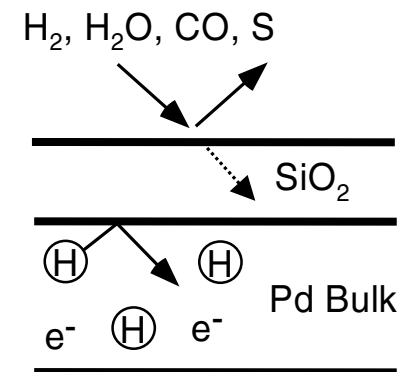
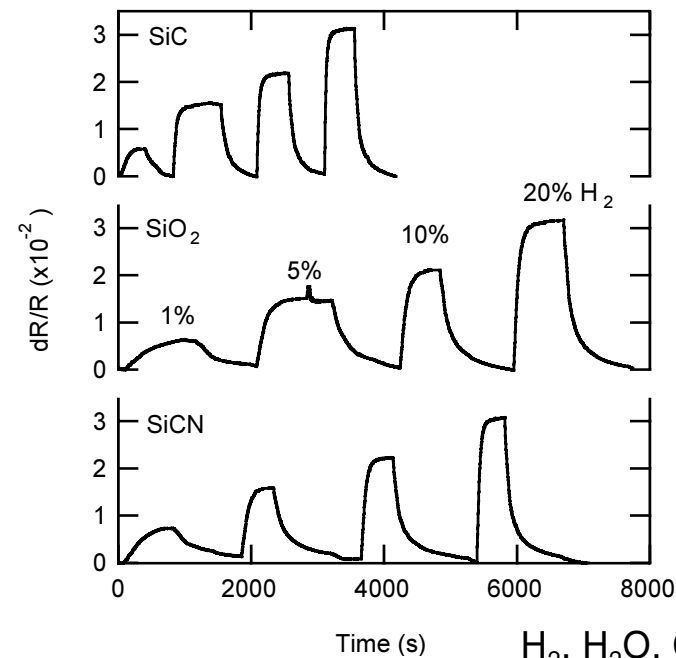
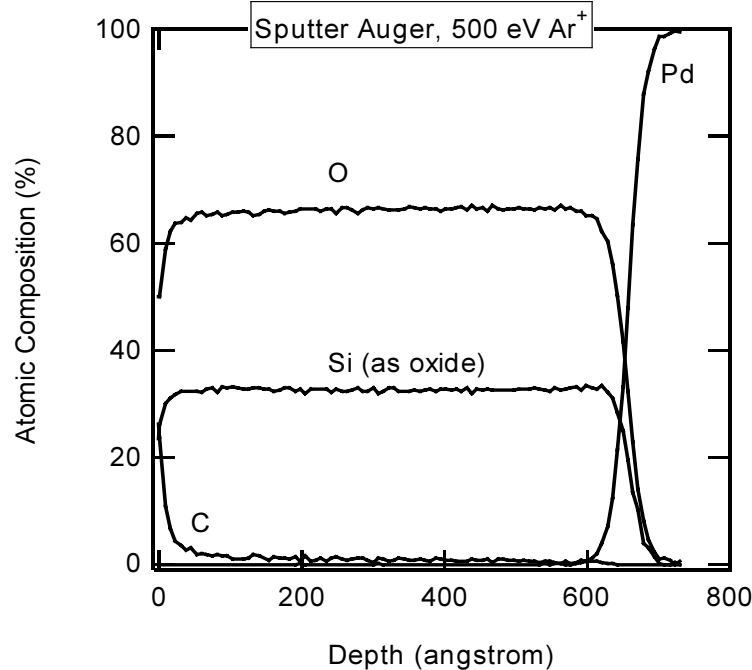
- **Modes governed by who's first**

- Site blocking
 - CO first, or simultaneous
- Trapping
 - H_2 first

- **Kinetically controlled phenomena**

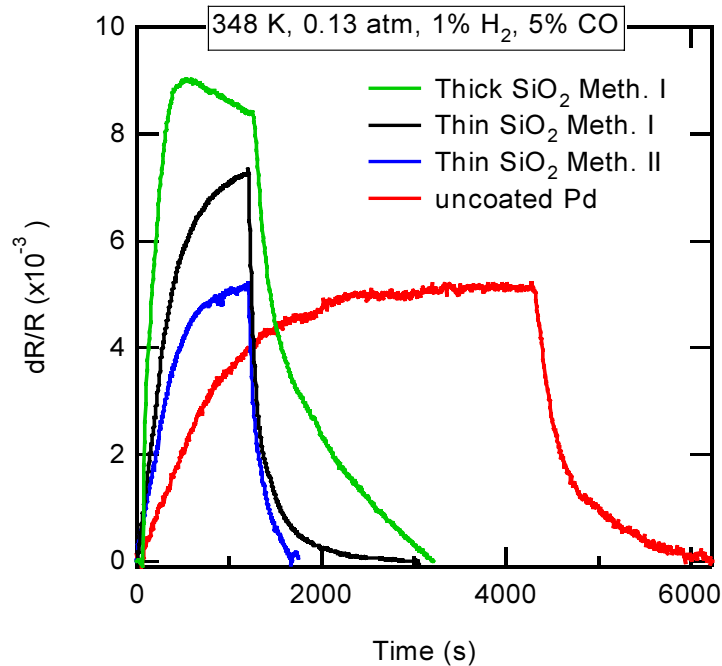


Inorganic Films May Mitigate Poisoning



- **Thick, dense oxides, nitrides, carbides**
 - Precise control of film properties
 - composition, thickness, morphology
- **Ultimate catalyst poison!**
 - Activity at buried interface or sizeable defects in film?

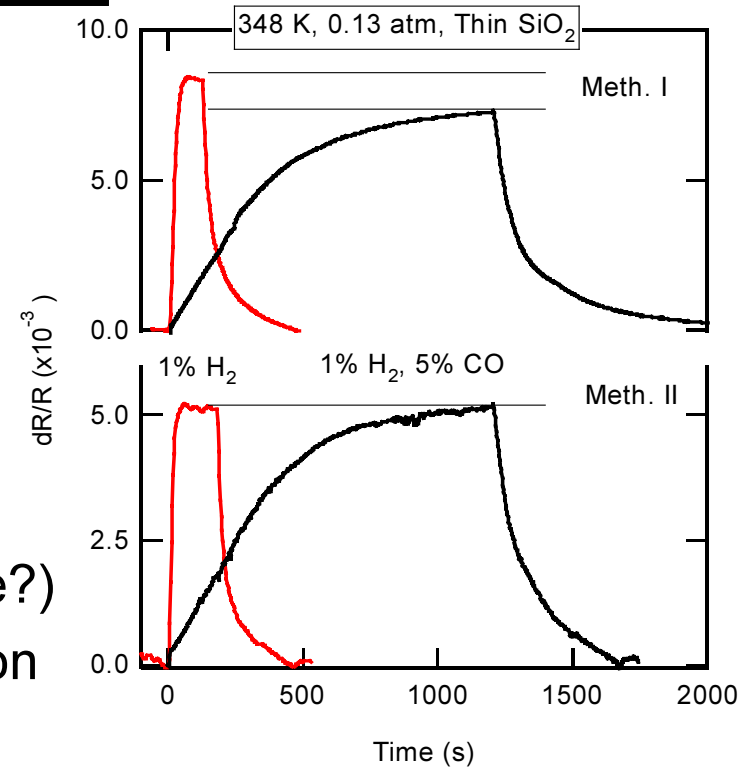
SiO₂ Coating - Response to H₂ + CO



Sensor	1/Response
Bare Pd	120
Thick Meth. I	4.2
Thin Meth. I	31
Thin Meth. II	39

■ Clear gains in sensor response times

- Factor of 3 to 30 times faster (or more?)
- May be possible to mitigate attenuation due to trapping / site blocking



Technical Progress and Outlook

Completed Project Milestones/Goals

Milestone		Due Date	Completion Date	Comments
PSU	Fabricate H ₂ -chemresistor test structures; vary alloy composition, incorporate membranes	10/01 3/02-1/03	9/01 11/02	completed
SNL	Construct laboratory testing facility	11/00 1/02	1/01 4/02	flow cell high-pressure cell
SNL	Develop surface chemistry models for predicting sensor performance	10/01	10/01	further modeling efforts abandoned
SNL	Characterize sensors, determine failure modes, evaluate design changes	1/03	12/02	completed
DCHT	Provide equipment for field tests	7/00 3/02	7/00 7/02	business failed
APCI	Upgrade and prepare field unit for pilot plant testing	2/02	9/02	completed
APCI	Pilot plant testing	12/00 7/02	12/00 4/03	completed

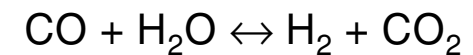
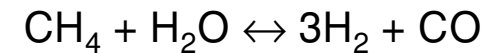
Hydrogen Cogeneration

- **Air Products & Chemicals**

- HyCO plants CA and LA
- H₂ content of process streams
 - Refinery feed stock
 - Hydrocarbon reformer
 - Shift reactors (HTS,LTS)

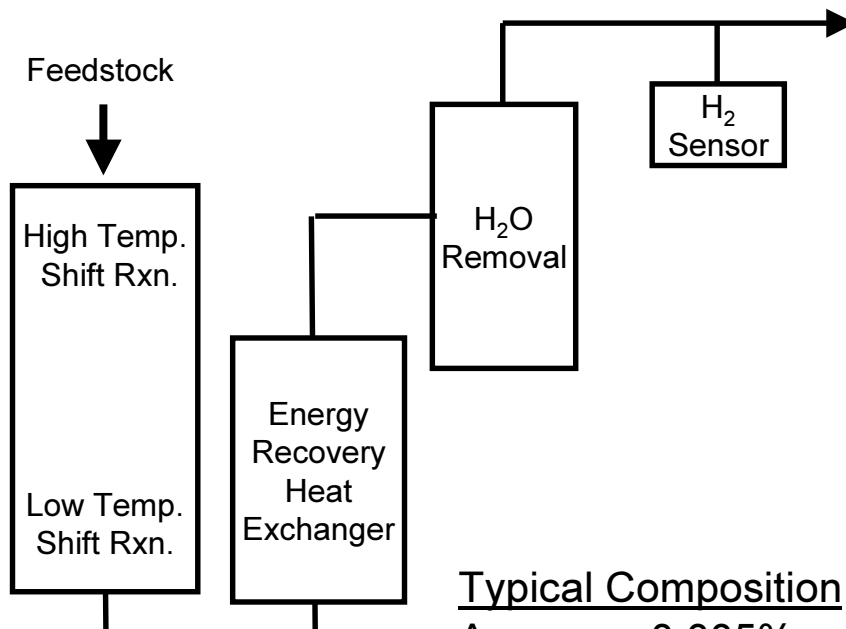
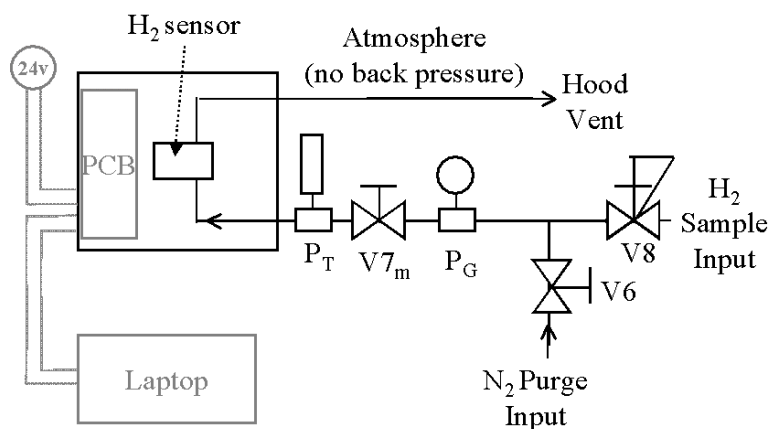
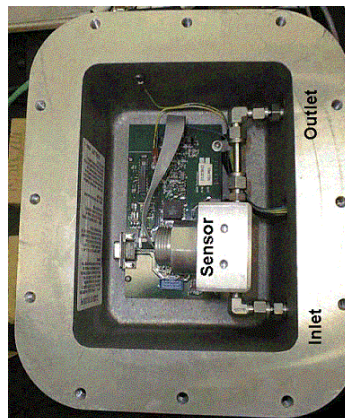
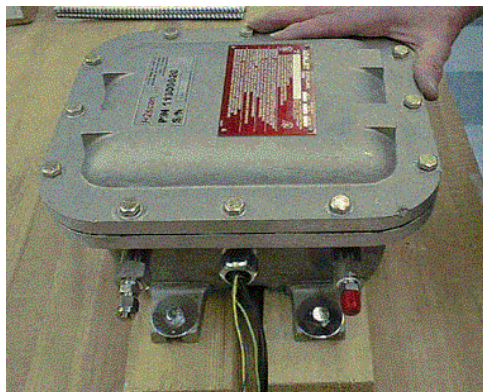
- **Potential benefit to plant operations**

- Redirect H₂-rich feed streams
- Optimize steam-to-carbon ratio
- Minimize gas venting
- Reduce power consumption



HTS/LTS Process Measurements

sensor

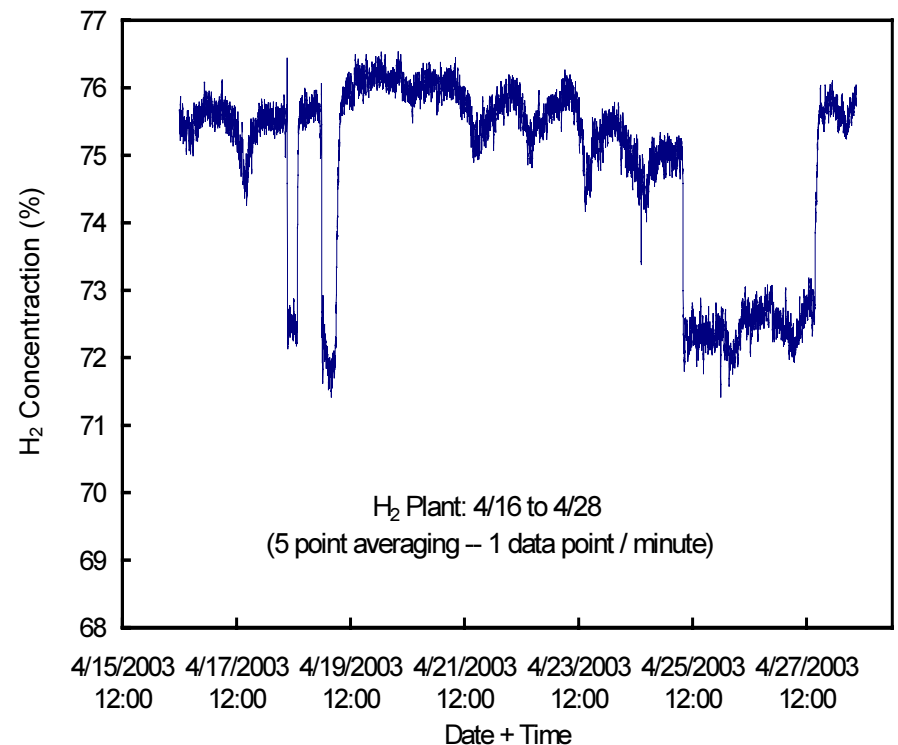


plant

Typical Composition	
Ar	0.005%
N ₂	0.04%
CO	0.2%
CH ₄	0.6%
H ₂ O	1.4%
CO ₂	22.2%
H ₂	75.6%
(by difference)	

HTS/LTS Process Measurements

- **Chemical resistor measurement in good agreement with:**
 - GC difference measurement
 - Batch sample analysis
- **Maintenance on O₂ feed lines showed 3% deviations in H₂ output**
- **Daily oscillations of H₂ observed for the first time**



Market Potential

- **Major chemical and petroleum manufactures have shown interest**
 - Tennessee Eastman-Chemicals
 - batch hydrogenation
 - Air Products & Chemicals
 - hydrogen and ammonia production
 - Exxon-Mobil
 - Dow
- **Program did generate intellectual property**
 - Service and licensing responsibilities may be assumed by APCI
- **Commercialization partner DCH Technologies**
 - Identified market opportunities however company failed in 2002

Market Potential

- **Measuring H₂ content of process streams critical to S&A community (Industries of the Future)**
 - Glass
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 - Chemicals
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- **Application outside Industries of the Future**
 - Advancing the H₂ economy
 - generation, storage, utilization

Programmatic Merit for H₂ Production

- **Improving energy efficiency for hydrogen cogeneration**
 - Measure H₂ in refinery feed and process streams
 - Redirect H₂-rich feed gas
 - Optimize steam-to-carbon ratio
- **Redirecting H₂ rich refinery feed**
 - Estimated improvement in efficiency is 0.4% per plant
 - assume 6 units installed
 - Save 1.24 BTU/SCF H₂ @ 0.5-1x10⁶ SCF H₂/day/plant
 - Save 2.2x10⁸ BTU/day in U.S. facilities
- **Plant optimization would yield even greater energy savings**

Programmatic Merit for Batch Hydrogenation

- **Batch hydrogenation**

- Monitor H₂ as a function of time
 - 1% improvement in sustained catalytic efficiency
 - Extend life of catalytic bed by 0.5 years

- **More than 400 hydrogenation facilities in U.S.**

- Save $\$1.5\text{-}2.5 \times 10^8/\text{year}$ @ $\$3.0\text{-}5.0 \times 10^5/\text{year/plant}$
- Extending intervals between catalyst replacement could save $\$2.4 \times 10^7/\text{year}$

- **Mass spectrometer installed cost $\$3.0 \times 10^5/\text{unit}$**

- **H₂ Solid state sensor installed cost $\$1.5 \times 10^4/\text{unit}$**

- Chemical resistor chips are a small fraction of the installed cost!

Summary

- **Recognized important relationships between processing and sensing environment to the application of H₂ chemical resistor technology**
- **Engineered solutions to barriers preventing industrial application**
 - Optimize alloy metal, composition, film morphology
 - No limit to potential coating technologies
 - inorganic, organic, combinations (sol-gels), functionalized (hydrophobic)
- **Established confidence within the industrial community by executing successful field trials**